

ABSTRACT OF THE DISCLOSURE

The invention regards to a microlithography projection objective for short wavelengths, preferably ≤ 193 nm, with an entrance pupil and an exit pupil

- 5 for the imaging of an object field in an image field, which represents a segment of a ring field, wherein the segment has an axis of symmetry and an extension perpendicular to the axis of symmetry, and the extension is at least 20, and preferably 25 mm.

- 10 The microlithography projection objective comprises
-- a first (S1), a second (S2), a third (S3), a fourth (S4), a fifth (S5), and a sixth mirror (S6) in centered arrangement relative to an optical axis, whereby
--each of these mirrors has a off-axis segment, in which light beams
15 impinge, which have been guided through the projection objective.

whereby

- as a function of the numerical aperture NA of the exit pupil, the diameter
20 of the off-axis segment of the first, second, third, fourth, fifth and sixth mirrors is $\leq 1200 \text{ mm} \cdot \text{NA}$.